

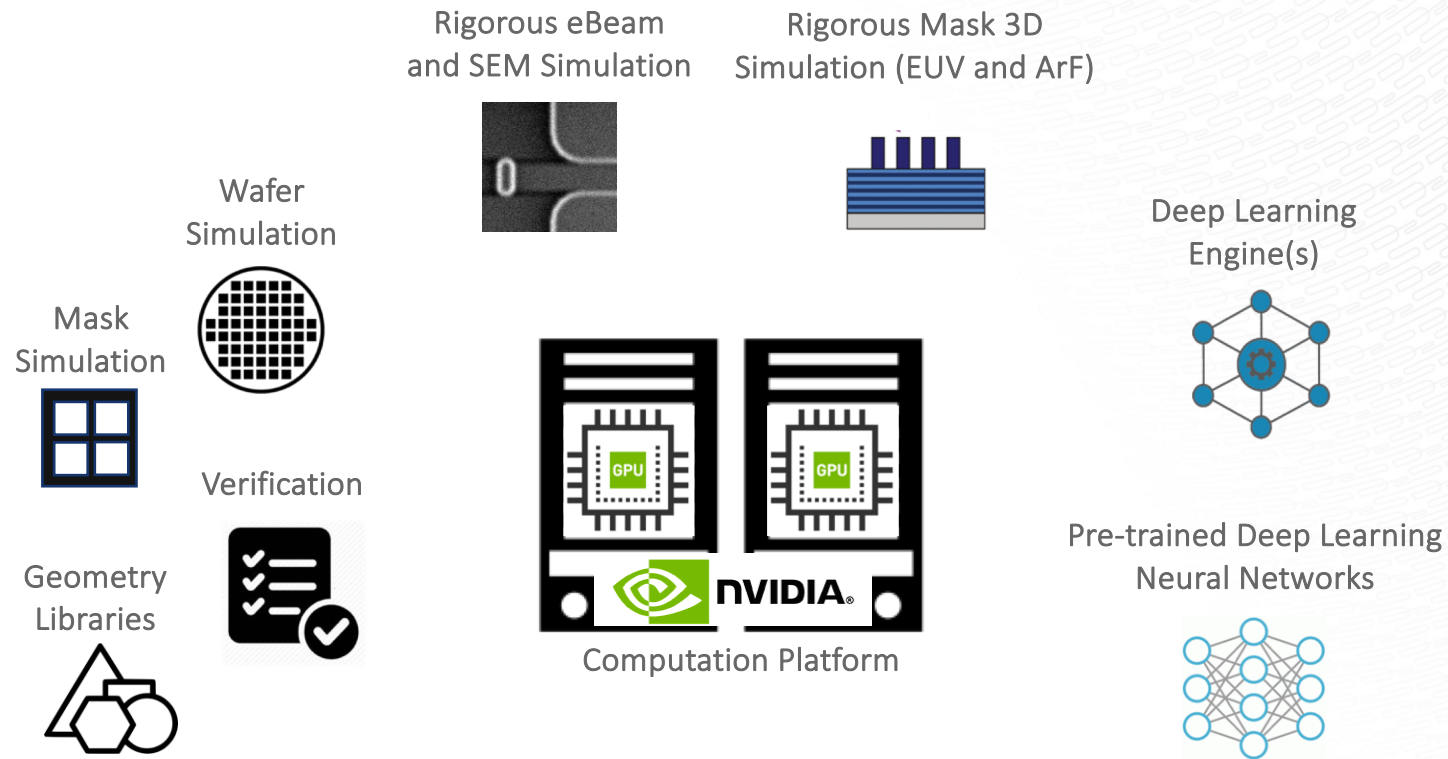


FEBRUARY 26, 2019 | LEO PANG, PHD

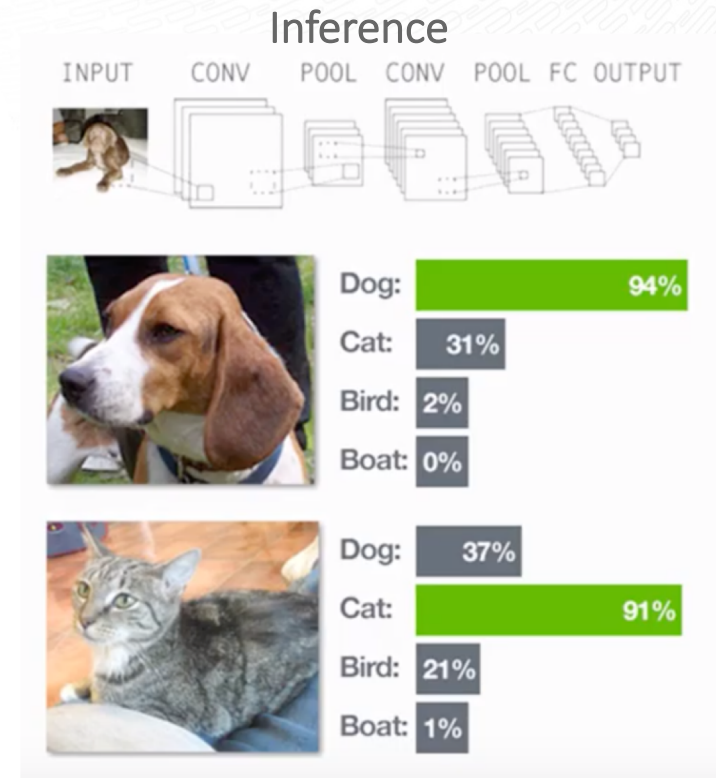
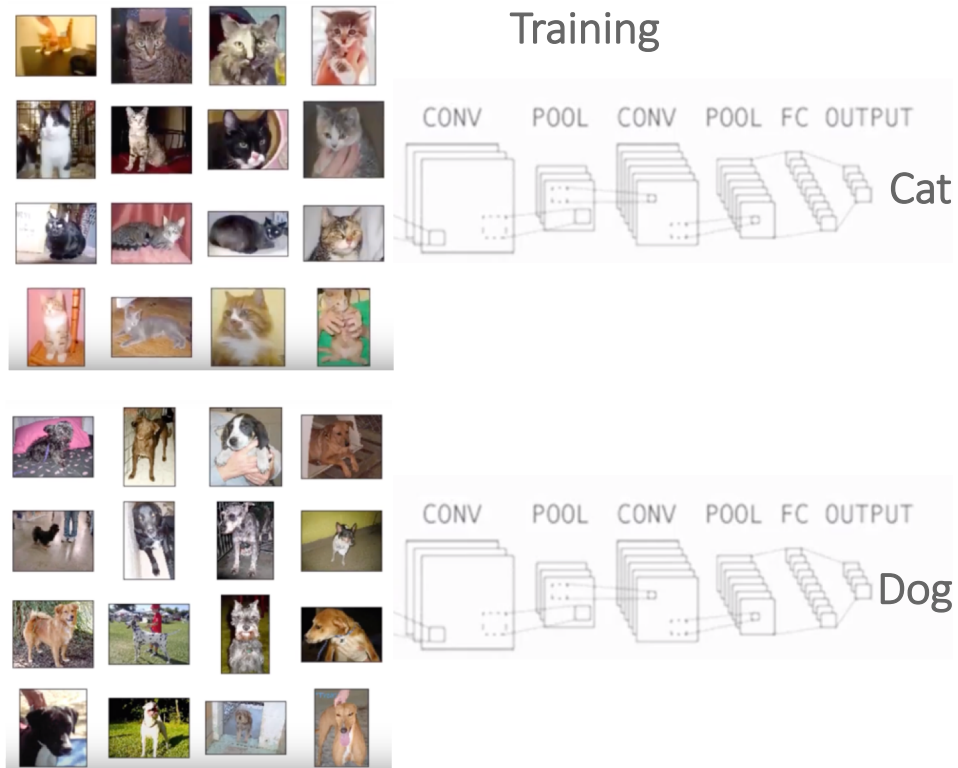
How GPU-Accelerated Simulation Enables Applied Deep Learning for Masks and Wafers

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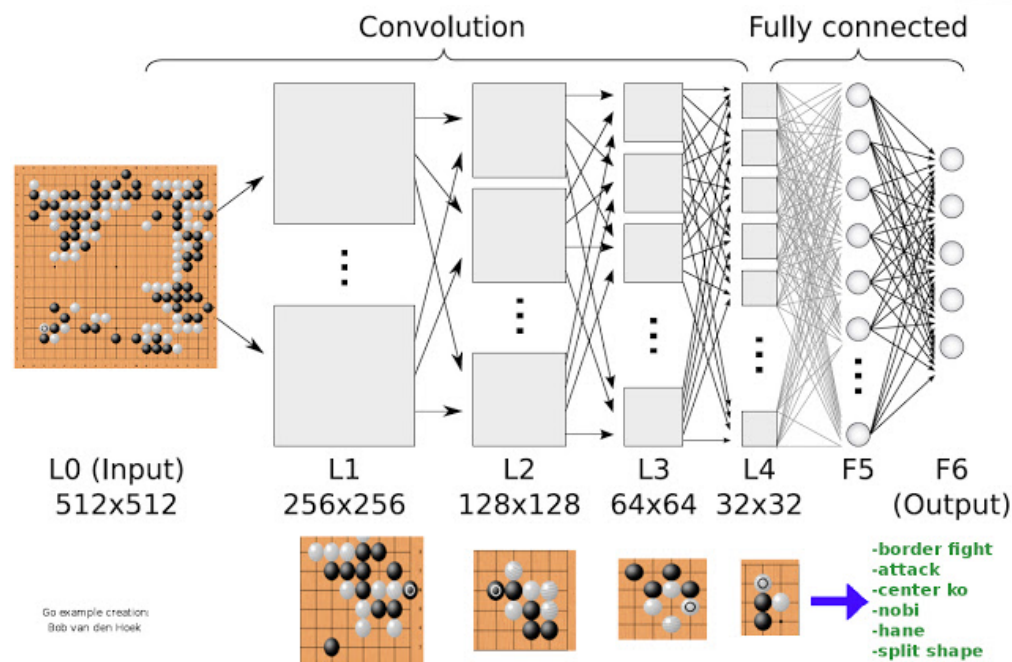
GPU-Accelerated Platform for Deep Learning (DL) to Boost Your Internal R&D



Deep Learning (DL) Doesn't "Reason" – It Pattern Matches



But With Tireless Learning From Pattern-Matching, Deep Learning (DL) Can “Out-think” Humans



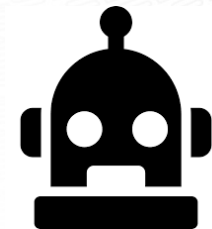
Source: Bob van den Hoek's blog, "Deep Learning: Sky's the Limit?"



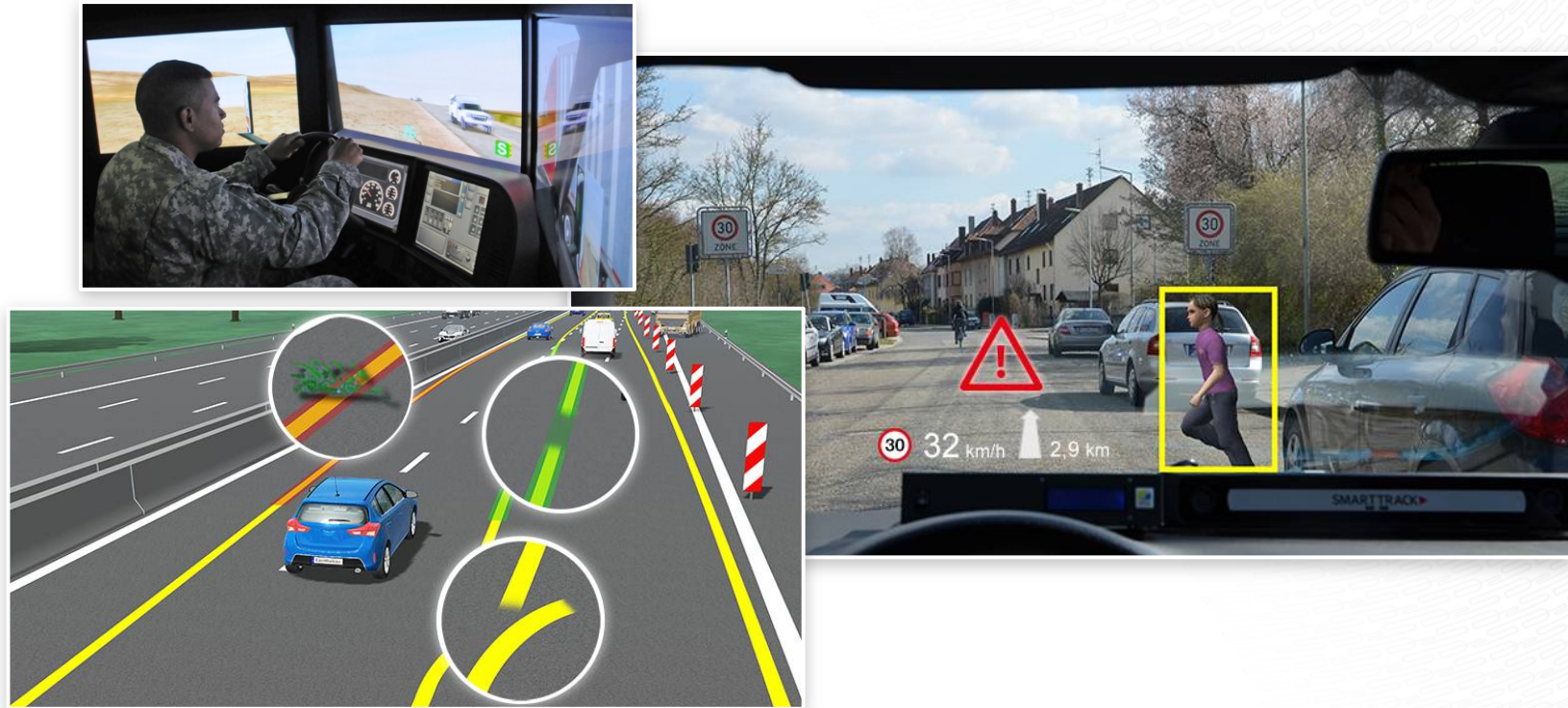
10K games
in life time



100M games
in 4~6 weeks



“Enough Data” Needed to Learn Similar Situations



But some situations are too dangerous or rare for “real life” training

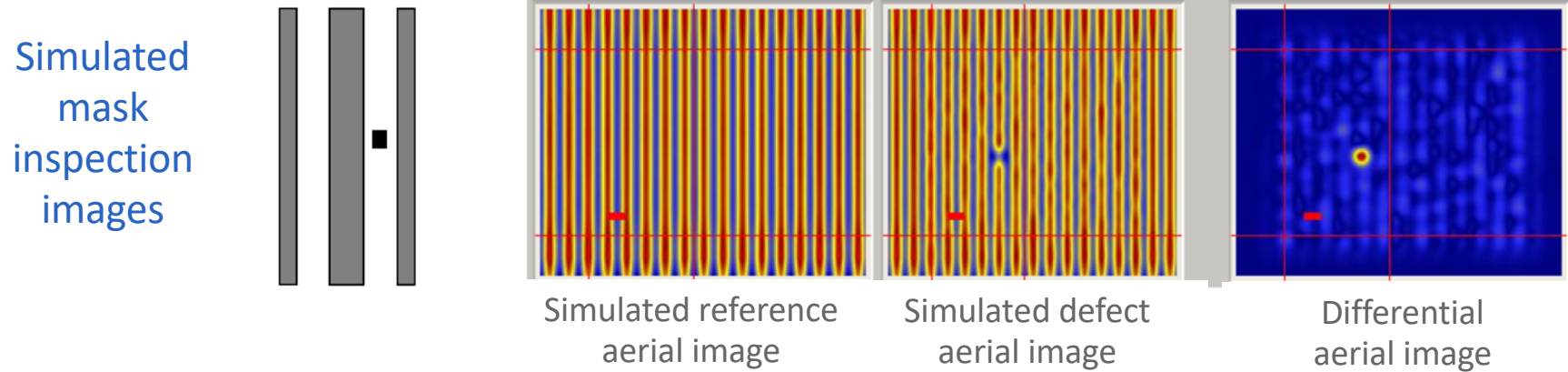


Simulation: Test, Validate Billions of Miles Safely

- Deep Learning (DL) training focuses on corner cases
 - Millions of similar “normal” driving miles don’t add to the learning
- Simulation allows combinations of effects to be automatically generated
 - Traffic, weather, accidents...
- Indispensable for debugging
 - Controlled environment
 - Easy fault insertion
 - Learning without machine time



Simulation Offers the Same Advantages for Deep Learning (DL) in Semiconductor Manufacturing

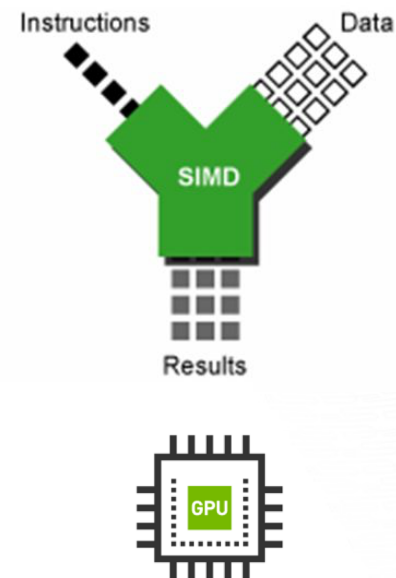
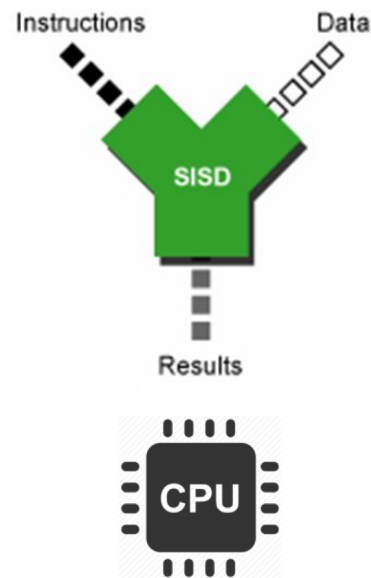


**Defects Are a Very Small Percentage of all masks and wafers,
But for Deep Learning Training, We Need A LOT of Them**

Source: L. Pang, et. al, "Computational inspection applied to a mask inspection system with advanced aerial imaging capability", SPIE Advanced Lithography, 2010



GPU Excels at Simulation and Training for Deep Learning



 **Caffe2**

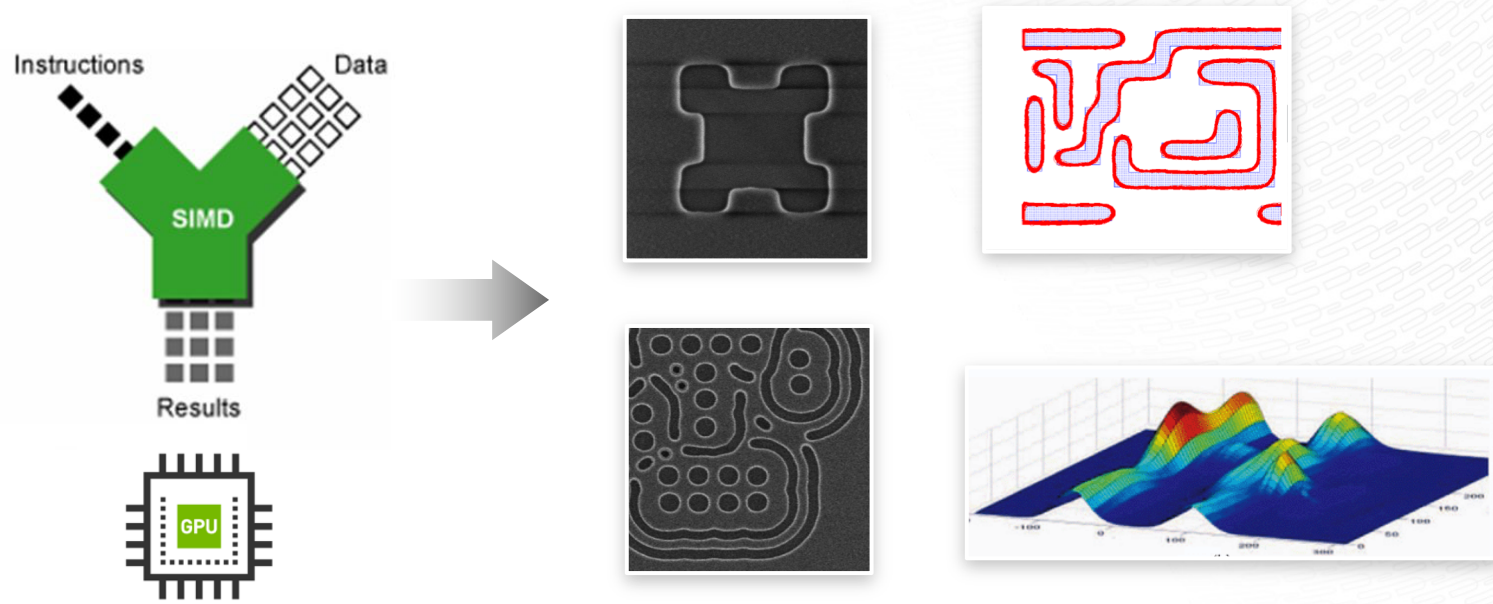
 PyTorch

 **TensorFlow**™

YOLO



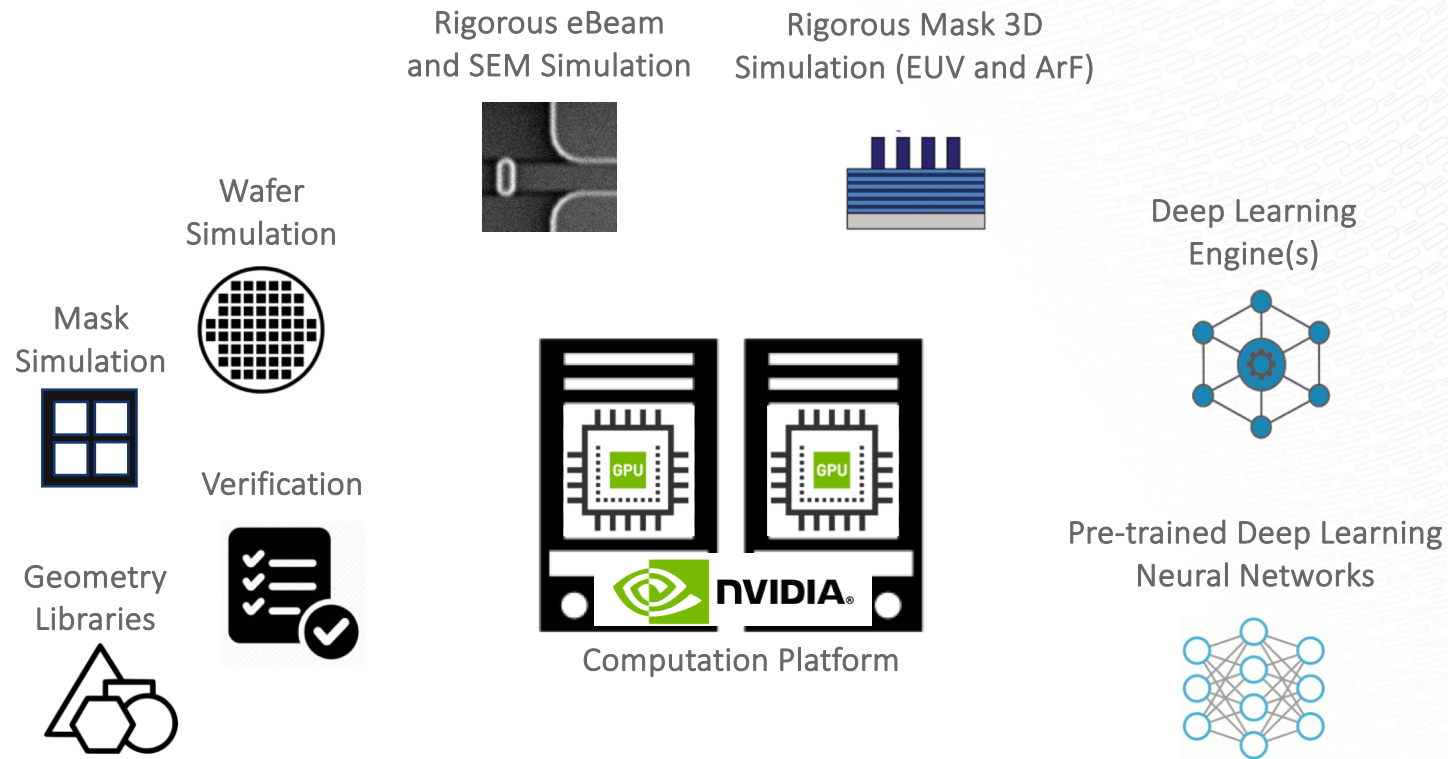
GPU Also Excels at Mask and Wafer Simulation



GPU (SIMD) is perfect for pixel data, which is shape-independent



GPU-Accelerated Platform for Deep Learning (DL) to Boost Your Internal R&D



Platform Application: D2S Project at CDLe

CENTER
FOR DEEP LEARNING
IN ELECTRONICS
MANUFACTURING

A PARTNERSHIP OF

NUFLARE

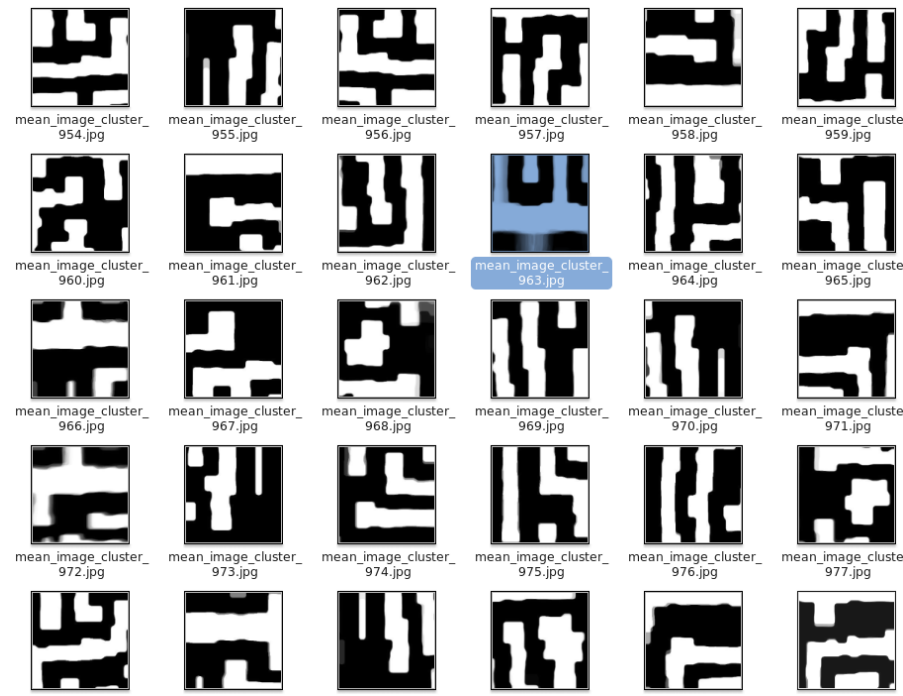
MYCRONIC

D2S

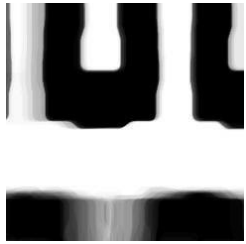
D2S

DL Mask Pattern Classifier Trained with Simulated Mask Pattern and Autoencoder

Different Groups
Classified by
Deep Learning

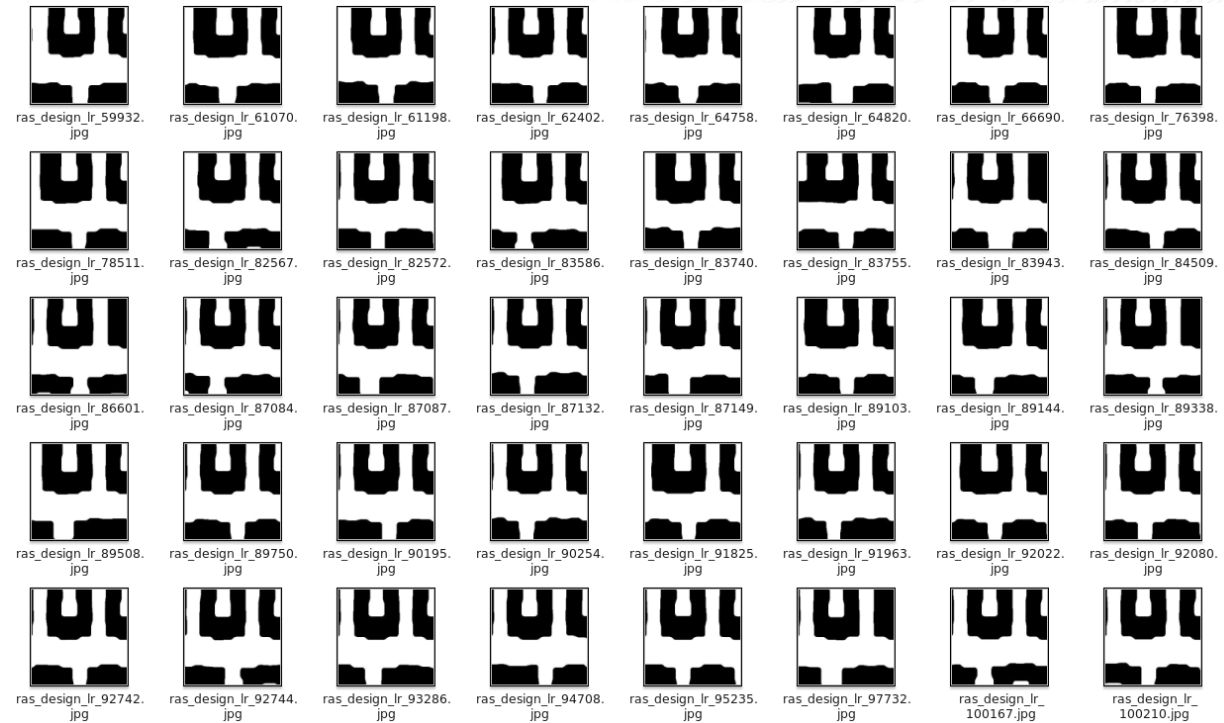


DL Mask Pattern Classifier Trained with Simulated Mask Pattern and Autoencoder



Sum images of
Group 963

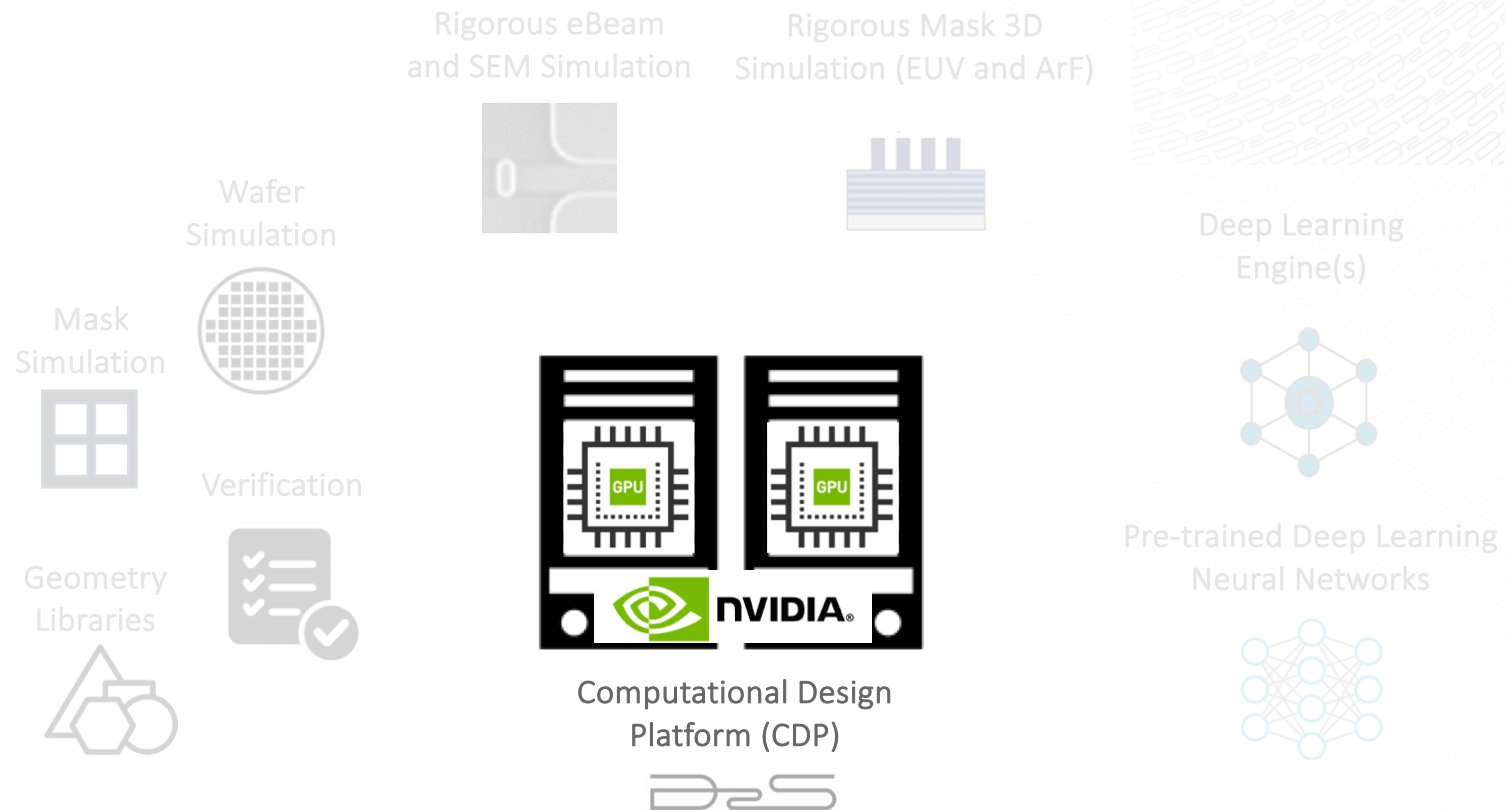
Each Instance
of Group 963



DL Mask Pattern Classifier Trained with Simulated Mask Pattern and Autoencoder



GPU-Accelerated Platform for Deep Learning (DL) to Boost Your Internal R&D

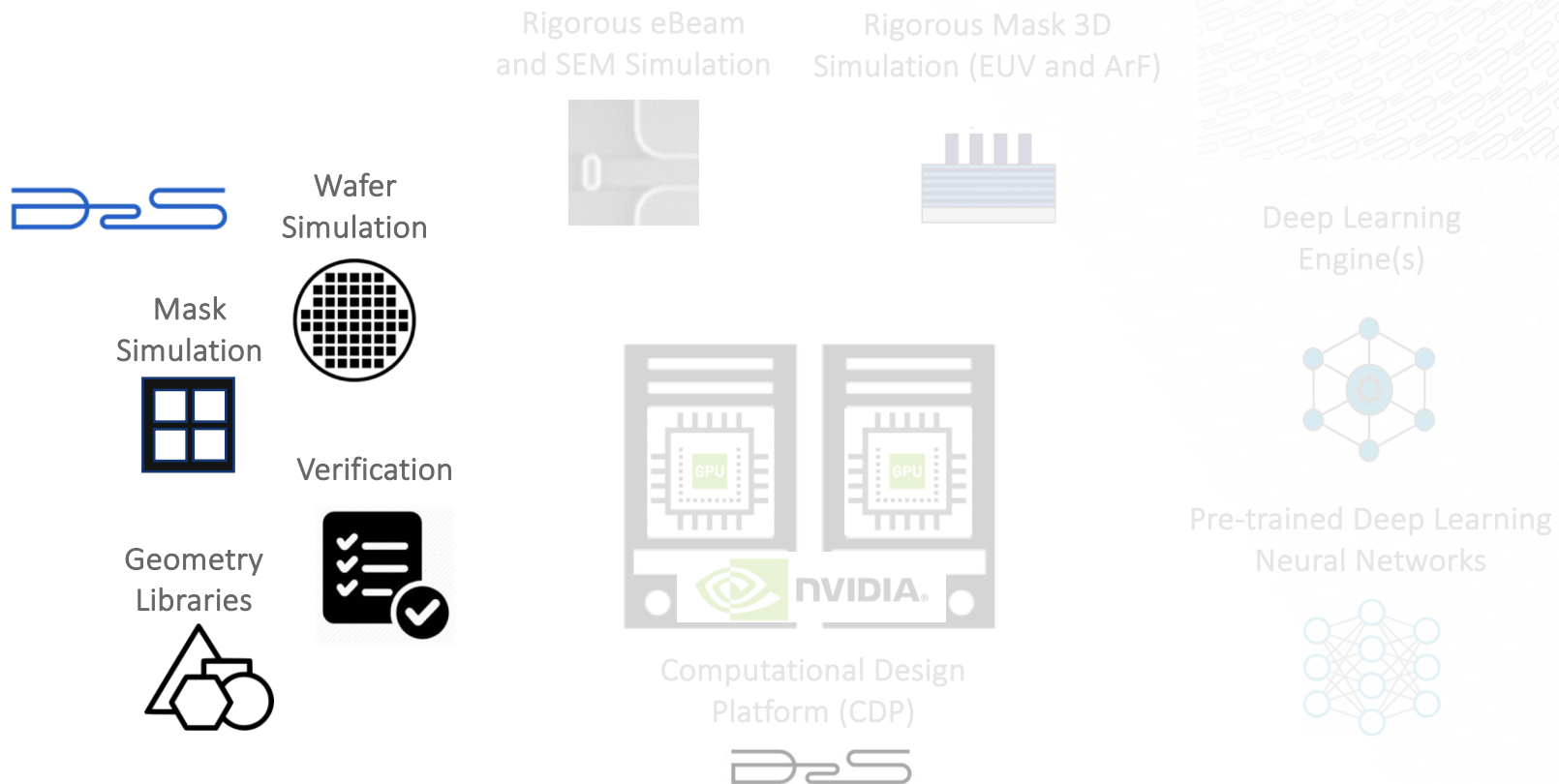


GPU-Accelerated Computational Design Platform

- For Deep Learning Acceleration at CDLe
 - 500 TFLOPS SP computing power with NVIDIA V100
 - Reliable, Redundant, Recoverable for 24/7 Clean Room Operations
- Integrated Solution for GPU-Accelerated Deep Learning



GPU-Accelerated Platform for Deep Learning (DL) to Boost Your Internal R&D



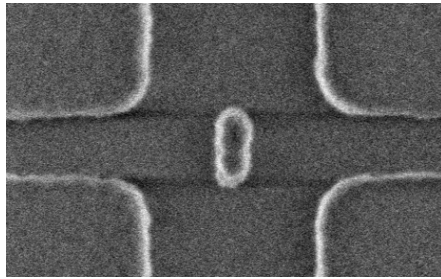
D2S TrueMask®: GPU-Accelerated Curvilinear Mask/Litho Simulators, Geometry Engine, Verification for DL Training

GPU-Accelerated Platform for Deep Learning (DL) to Boost Your Internal R&D

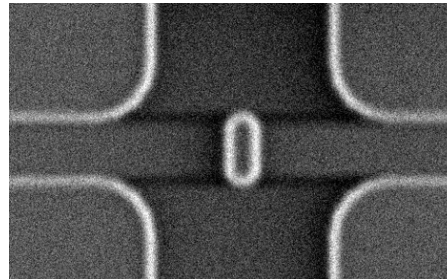


GPU-Accelerated Rigorous eBeam/SEM Simulators and EUV Mask 3D Simulators from Partners for DL Training

aBeam
technologies

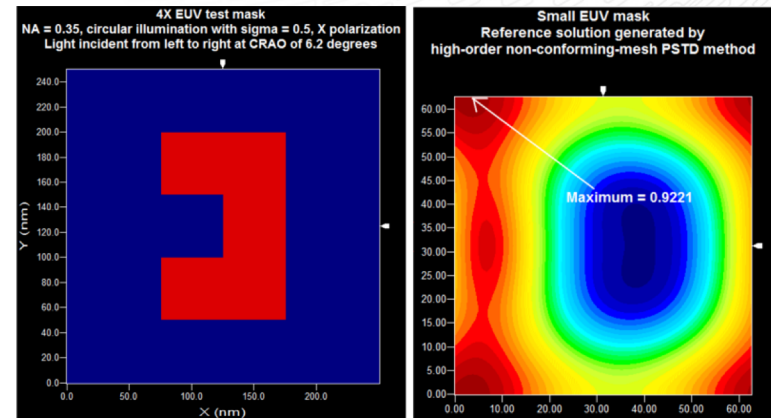


Actual SEM



Simulated SEM

Fastlitho

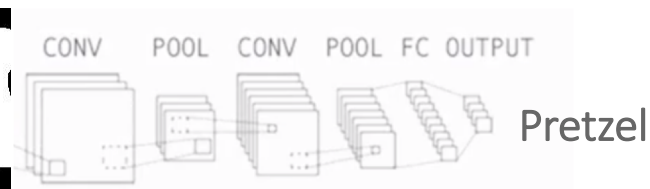
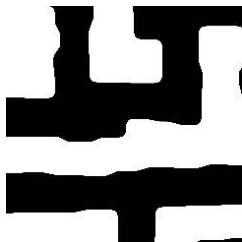
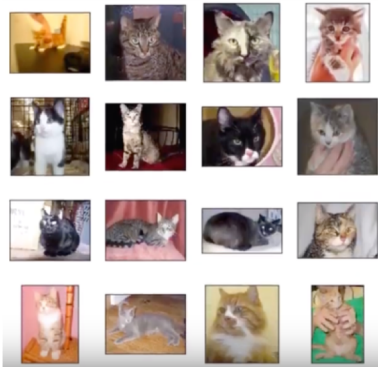


Fast Rigorous EUV Mask
3D Simulation

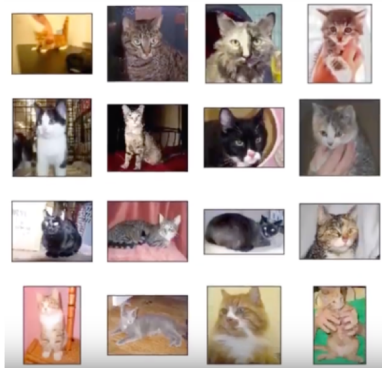
GPU-Accelerated Platform for Deep Learning (DL) to Boost Your Internal R&D



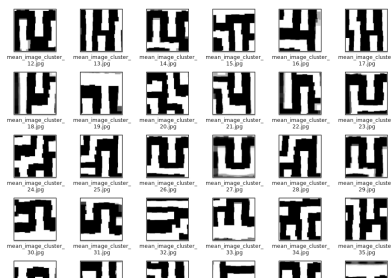
Pre-Trained Deep Learning Neural Network Models for Masks and Wafers



Pre-Trained Deep Learning Neural Network Models for Masks and Wafers



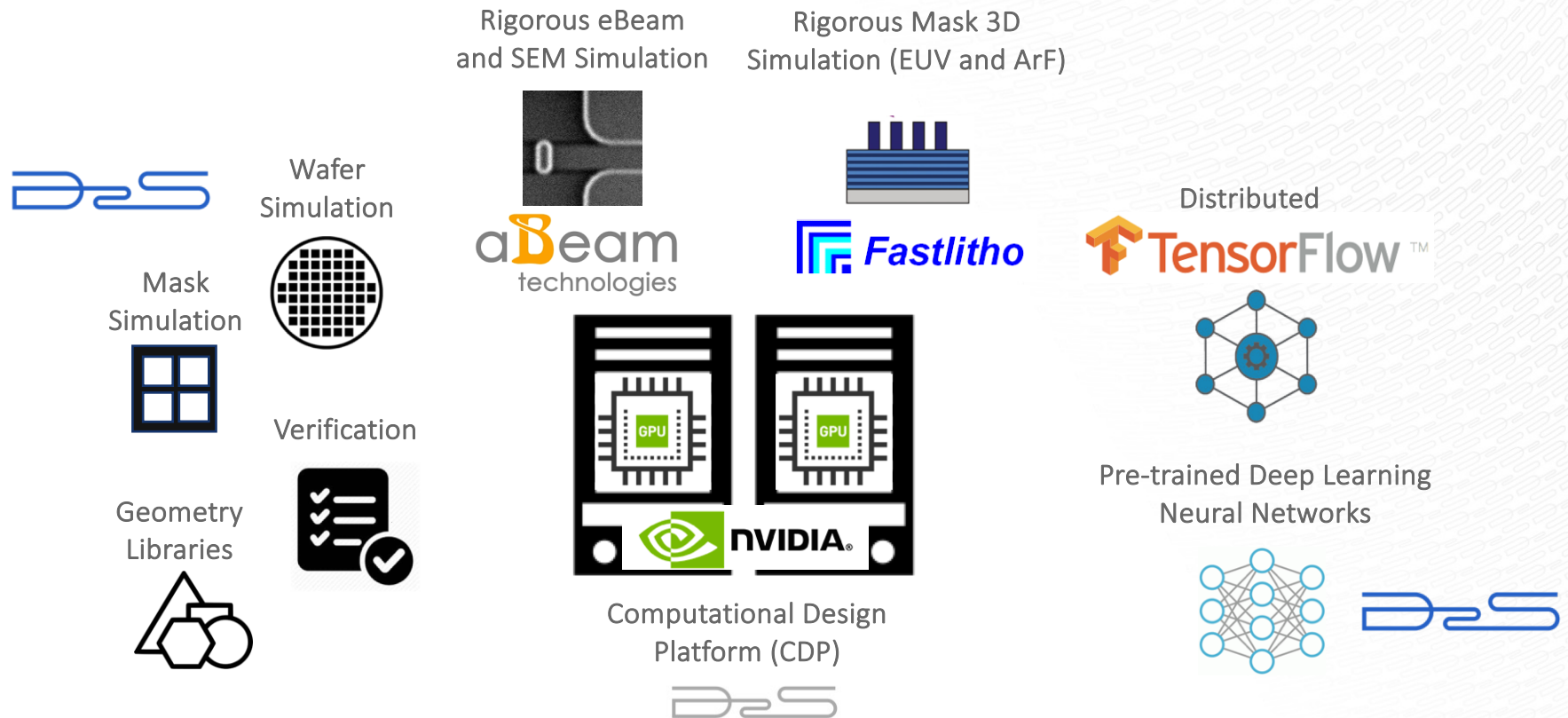
The network training required to identify a cat is very different from the network training required to identify a wafer defect



Pre-trained DL Neural Network Model for Mask and Wafer

Hotspot/Defect Classification

GPU-Accelerated Platform for Deep Learning (DL) to Boost Your Internal R&D



DES